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Application No.	Applicant(s)
10/720,730	SCHLOSSER et al.
Examiner	Art Unit
Lee, Calvin	2825
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ner.	
4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)	
6. ☐ Interview Summary Paper No./Mail Dat 08), 7. ☐ Examiner's Amendn	
	Examiner Lee, Calvin Pears on the cover sheet with the council (OR REMAINS) CLOSED in this application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application is subject to 3 and MPEP 1308. The sheet is application in the sheet is application. The sheet is application in the sheet is application. The sheet is a sheet is application in the sheet is a sheet is application. The sheet is a shee

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Application No: 10/720,730

Docket: INFN/0037

SCHLOSSER et al.

OFFICE ACTION

Allowable Subject Matter

Claims 1-6 and 25-31 are allowed. Following is the reason for allowance:

The closest prior art, US 5,888,864 to Koh et al, discloses portions of a polysilicon layer (which is located on the surface of active regions 1b) [Fig. 1E] disposed between a plurality of lower source/drain regions 3 and a plurality of upper source/drain regions 11 [cols. 3-4]. US 6,800,898 to Cappelani et al discloses forming a plurality of word lines W over a plurality of electrodes V, which are separated by lower source/drain regions S/Du, channels, and upper source/drain regions S/Do [Fig. 5 and col. 8]. None of the cited arts teaches or suggests, inter alia, etching trenches to form a plurality of parallel ribs having strips of source/drain material disposed thereon; and forming a plurality of word lines over and cross-wise with respect to the ribs.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance.

Contact Information

Any inquiry concerning this communication from the Examiner should be directed to *Calvin Lee* at (571) 272-1896 on Mondays thru Thursdays 6:30-4:30PM. If attempts to reach the examiner by telephone are unsuccessful, Art Unit 2818's Supervisory Patent Examiner *David Nelms* can be reached at (571) 272-1787. The fax phone number for the organization (where this application is assigned to) is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system at http://pair-direct.uspto.gov. Should you have questions on access to the PAIR system, contact the Electronic Business Center at (866) 217-9197.

CL

David Nelms
Supervisory Patent Examiner
Technology Center 2800